

IN THE CLAIMS

When entered this listing of claims will replace all claims previous presented in the application:

7. (currently amended) A method of making a supported mask that may be used in modifying a substrate, comprising:
obtaining a support that is not the substrate;
applying at least one layer of dielectric material to said support; and
exposing said layer to patterned light to substantially cause removal of said layer from said support in exposed areas,
wherein the exposing causes ablating of the exposed areas of the layer.

8. (previously presented) The method as in claim 7 wherein the patterned light is UV light.

9. (canceled)